CNFULL (China (CN) Patents Full Text)

Subject Coverage

All patent-relevant areas of science and technology, i.e., all classes of the International Patent Classification

File Type

Full Text

Features

Thesauri	International Patent Classification (/IPC), Cooperative Patent Classification (CPC), European Patent Classification (/EPC)		
Alerts (SDIs)	Weekly or monthly (weekly is the default)		
CAS Registry Number® Identifiers	☐	Page Images	☐
Keep & Share	☑	SLART	☑
Learning Database	☐	Structures	☐

Record Content

- Full text of patent applications, granted patents, and utilities models published in People's Republic of China from 1985 onwards.
- Records are available about a week after publication date with the complete content
- Records contain bibliographic data including patent applicant and inventor, patent, application, priority, and related (PCT) application data, IPC, CPC and EPC classification codes, abstract, and full text of description and claims.
- Titles and abstracts are initially machine translated and about three month later replaced by human translated text; descriptions and claims are machine translated.
- Numeric values of over 30 physical and chemical properties are searchable in almost 400 unit variants in all full text fields.
- Database records comprise all documents published for one application.
- Clipped images (mostly front-page images) are also included, when available.
- Legal status data and family display formats from the INPADOCDB database are available.

File Size

- More than 18.4 million family records with more than 24.8 million publications (07/2020)
- More than 17.7 million front page images (07/2020)

Coverage

1985–present

Updates

Weekly

Language

English

Database Producer

LexisNexis Universio BV
Galileiweg 8
2333 BD Leiden
The Netherlands
Phone: (+31) 88-6390000
Email: customersupport@univentio.com
Copyright Holder

Database Supplier	FIZ Karlsruhe STN Europe P.O. Box 2465 76012 Karlsruhe Germany Phone: +49-7247-808-555 Fax: +49-7247-808-259 Email: helpdesk@fiz-karlsruhe.de
Sources	Patent applications, granted patents, and utilities models published by the State Intellectual Property Office in the People's Republic of China
User Aids	• Online Helps (HELP DIRECTORY lists all help messages available) • STNGUIDE
Clusters	• AEROTECH • ALLBIB • AUTHORS • CORPSOURCE • ENGINEERING • FULLTEXT • HPATENTS • NPS • PATENTS • PNTTEXT STN Database Cluster information: http://www.stn-international.com/en/customersupport/customer-support#cluster+%7C+subjects+%7C+features

Search and Display Field Codes

If multiple search terms are linked with and AND-operator, all terms are searched in the complete database record, i.e. in all publications referring to one application. For a search in a specific publication of the record, connect the search term and the patent kind code with the (L)-proximity operator, e.g.
S BOREHOLE/AB,TI,CLM (L) CNA/PK limits the search to Chinese applications CNA.

Fields that allow left truncation are indicated by an asterisk (*).

General Search Fields

Search Field Name	Search Code	Search Examples	Display Codes
Basic Index* (contains single words from title (TI), abstract (AB), detailed description (DETD), claims (CLM), and main claims (MCLM) fields)	None or /BI	S TRANSISTOR AND ELECTRODE S ACOUSTIC SENSOR S ?TRANSFER?	TI, AB, DETD, CLM, MCLM
Abstract*	/AB	S BOREHOLE/AB	AB
Accession Number	/AN	S 2010006109/AN	AN
Application Country (WIPO code and text)	/AC	S CN/AC	AI
Application Date **(1)**	/AD	S AD=JAN 2008	AI
Application Number **(2)**	/AP (or /APPS)	S CN 2011-10135271/AP S CN 2011-10135271/APPS	AI
Application Year **(1)**	/AY	S AY>=2000	AI
Claims*	/CLM	S DERIVATION/CLM	CLM
Cooperative Patent Classification **(3)**	/CPC	S C12N0009/CPC	CPC
Cooperative Patent Classification, Action Date	/CPC.ACD	S 20121113/CPC.ACD	CPC.TAB
Cooperative Patent Classification, Keyword	/CPC.KW	S C12N0009/CPC (S) I/CPC.KW	CPC.TAB
Cooperative Patent Classification, Version	/CPC.VER	S 20130101/CPC.VER	CPC.TAB
Document Type (code and text)	/DT (or /TC)	S P/DT S PATENT/DT	DT
Entry Date **(1)**	/ED	S ED=FEB 2011	ED
Entry Date of Fulltext **(1)**	/EDTX	S 20120324/EDTX	EDTX
European Patent Classification **(3)**	/EPC (or /ECLA)	S A01B0001-02H/EPC	EPC
Field Availability	/FA	S AB/FA	FA
Graphic Image Size **(1)**	/GIS	S L1 AND 700-800/GIS	GIS
International Patent Classification (ICM, ICS, IPCI, IPCR) **(3)**	/IPC	S A01B001/IPC	ICM, ICS, IPCI, IPCR
International Patent Classification (ICM, ICS)	/IC	S A45D/IC	IC, ICM, ICS
Inventor	/IN (or /AU)	S ZHANG TING /IN S ZHANG?/IN	IN
Inventor, Country (WIPO code and text)	/IN.CNY	S CN/IN.CNY	IN, IN.CNY
IPC, Initial	/IPCI	S B21B0001/IPCI	IPCI, IPC
IPC, Keyword Terms	/IPC.KW	S INITIAL/IPC.KW	IPC.TAB
IPC, Main	/ICM	S A62B037-00/ICM	ICM, IC
IPC, Reclassified	/IPCR	S B21C0037-20/IPCR	IPCR, IPC
IPC, Reform	/IPC.REF	S A01B0001-04/IPC.REF	IPC.TAB
IPC, Secondary	/ICS	S A01M029-10/ICS	ICS, IC
IPC, Version	/IPC.VER	S 7/IPC.VER	IPC.TAB
Language (code and text)	/LA	S CN/LA S ENGLISH/LA	LA
Language, Filing (code and text)	/LAF	S EN/LAF S CHINESE/LAF	LAF
Main Claim*	/MCLM	S ?FRACTURE?/MCLM	MCLM
Number of Claims **(1)**	/CLMN	S 5-7/CLMN	CLMN
Number of Paragraphs in DETD (Detailed Description) **(1)**	/DETN	S DETN<10	DETN

General Search Fields (cont'd)

Search Field Name	Search Code	Search Examples	Display Codes
Patent Applicant/Patentee **(4)**	/PA (or /CS)	S HUAWEI TERMINAL CO LTD /PA	PA
Patent Applicant, Country	/PA.CNY	S CN/PA.CNY	PA, PA.CNY
Patent Country (WIPO code and text)	/PC	S CN/PC	PI
Patent Information Publication Type	/PIT	S CNA UNEXAMINED APPLICATION FOR A PATENT FOR INV./PIT	PIT
Patent Kind Code	/PK	S CNA/PK	PI
Patent Number **(2)**	/PN (or /PATS)	S CN 102326444/PN	PI
Patent Number, Original	/PNO	S CN100358571/PNO	PNO
Patent Number/Kind Code	/PNK	S CN102326444 A/PNK	PI
Physical Properties	/PHP	S VOLT/PHP (S) TOUCH SCREEN/BI	KWIC
Priority Country (WIPO code and text)	/PRC	S CN/PRC S CHINA/PRC	PRN
Priority Date **(1)**	/PRD	S PRD=MAY, 20 2003 S 20030520/PRD	PRN
Priority Date, First **(1)**	/PRDF	S 20010614/PRDF	PRN
Priority Number **(2)**	/PRN	S DE2004-102004063820/PRN	PRN
Priority Number, Original	/PRNO	S US10001608P/PRNO	PRNO, PRAO
Priority Year **(1)**	/PRY	S 2003/PRY	PRN
Priority Year, First **(1)**	/PRYF	S 2003-2004/PRYF	PRN
Publication Date **(1)**	/PD	S PD=JAN-FEB 2008	PI
Publication Year **(1)**	/PY	S PY>2008 AND L1	PI
Related Patent Country	/RLC	S WO/RLC	RLI
Related Application Number	/RLN	S WO2005-CN1971/RLN	RLI
Related Application Date **(1)**	/RLD	S 20050329/RLD	RLI
Related Application Year **(1)**	/RLY	S 2005/RLY	RLI
Title *	/TI	S FLUID###/TI	TI
Update Date **(1)**	/UP	S UP=APRIL 2012	UP

(1) Numeric search field that may be searched using numeric operators or ranges.
(2) By default, patent numbers, application and priority numbers are displayed in STN Format. To display them in Derwent format, enter SET PATENT DERWENT at an arrow prompt. To reset display to STN Format, enter SET PATENT STN.
(3) An online thesaurus is available in this field.
(4) Search with implied (S) proximity is available in this field.

Super Search Fields

Enter a super search code to execute a search in one or more fields that may contain the desired information. Super search fields facilitate crossfile and multifile searching. EXPAND may not be used with super search fields. Use EXPAND with the individual field codes instead.

Search Field Name	Search Code	Fields Searched	Search Examples	Display Codes
Application Number Group	/APPS	AP, PRN	S 2010AU-202547/APPS	AI, PRAI, APPS

Property Fields (1)

In CNFULL a numeric search for a specific set of physical properties (/PHP) is available within the full text fields (TI, AB, DETD and CLM). The numeric values are not displayed as single fields, but highlighted within the hit displays.
Use EXPAND/PHP to search for all available physical properties. A search with the respective field codes will be carried out in all database fields with English text. The /PHP index contains a complete list of codes and related text for all physical properties available for numeric search.

Field Code	Property	Unit		Search Examples
/AOS	Amount of substance	Mol		S 10/AOS
/BIR	Bit Rate	Bit	(Bit)	S 100000-160000/BIR
/BYR	Byte Rate	Byte	(Byte)	S BYR<300000
/CMOL	Molar concentration (Molarity) (Concentration, amount of substance)	mol/l		S MOLYBD?/BI (S) 2/CMOL
/CON	Conductance	S	(Siemens)	S 1E-2/CON
/DEG	Degree	Degree		S (POLARI? (S) ANGLE)/BI (S) 45/DEG
/DEN	Density (Mass Density)	Kg/m3		S 5E-3-10E-3/DEN
/DV	Viscosity, dynamic	Pa s		S DV>5000
/ENE	Energy	J	(Joule)	S L1 AND 10000/ENE
/FOR	Force	N	(Newton)	S 50 N/FOR
/FRE	Frequency	Hz	(Hertz)	S ANALY?/CLM (10A) 0-3/FRE
/KV	Viscosity, kinematic	m2/s		S LUBRICANT/BI (S) 10E-5/KV
/LUME	Luminous Emittance/Illuminance	Lux		S 10-50/LUME
/LUMF	Luminous Flux (Luminous Power)	Lumen		S L74 (S) LUMF>70
/LUMI	Luminous Intensity	Candela		S 5<LUMI<15
/M	Mass	Kg	(Kilogram)	S ALLOY/BI (30A) 1E-10-1E-5/M
/MFL	Mass Flow (Mass Transfer)	Kg/s		S FEEDING (5A) 100-1000/MFL
/MFS	Magnetic Field Strength (Magnetic Flux Density)	Tesla		S MAGNET?/BI (10W) 5<MFS<7
/MW	Molar Mass	g/mol		S 2000-3000 G/MOL/MW
/PER	Percent (Proportionality)	Percent		S (TITAN? (3A) DIOXID?)/CLM (S) 5/PER
/PHV	pH	pH		S 7.4-7.6/PHV
/POW	Power	W	(Watt)	S (SOLAR? OR PHOTOVOLTAIC?)/BI (10A) 5-10/POW
/PRES (or /P)	Pressure	Pa	(Pascal)	S (VACUUM (5A) DISTILL?)/BI (S) 1000-1100/PRES
/RAD	Radioactivity	Bq	(Becquerel)	S 10-100/RAD
/RES	Electrical Impedance/resistance	Ohm		S CERAMIC/CLM (P) 1-8/RES
/SAR	Area /Surface Area	m2		S (COATING? OR FOIL?)/BI (S) 10-100/SAR
/SCO	Spring Constant	N/m		S (ALUMINUM OR ALUMINIUM)/BI (20A) 10000-50000/SCO
/SIZ	Size	m	(Metre)	S ?CARBON?/CLM (S) 3E-9/SIZ
/ST	Surface Tension	J/m2		S 1-5 J/M**2 /ST
/TEMP (or /T)	Temperature	K	(Kelvin)	S (REACTION? (25A) PHOSPHAT?) (S) 300 K /TEMP
/TIM	Time	S	(Second)	S ?INCUB?/CLM (10W) 10-50/TIM
/VEL (or /V)	Velocity	m/s	(Metre per Second)	S SPEED/BI (S) 5E-3 M/S - 20E-3 M/S /VEL
/VELA	Velocity, angular	rpm		S ANG?/CLM (S) VELA>10
/VOL	Volume	m3		S ?FUSION?/BI (15A) 3E-8 M**3 - 5E-8 M**3 /VOL
/VOLT	Voltage	V	(Volt)	S CALIBRAT?/BI(10A) 5E-3<VOLT<7E-3

(1) Exponential format is recommended for the search of particularly high or low values, e.g. 1.8E+7 or 1.8E7 (for 18000000) or 9.2E-8 (for 0.000000092).

International Patent Classification (/IPC) Thesaurus

The classifications, validity and catchwords for the main headings and subheadings from the current (8th) edition of the WIPO International Patent Classification (IPC) manual are available. The classifications from the previous editions (1-7) are also available as separate thesauri. To EXPAND and SEARCH in the thesauri for editions 1–7, use the field code followed by the edition number, e.g., /IPC2, for the 2nd edition. Catchwords are included only in the thesauri for the 8th, 7th, 6th, and 5th editions.

Code	Content	Examples
ADVANCED (ADV)	Advanced Codes for the Core Level IPC Code	E A61K0006-02+ADVANCED/IPC
ALL	All Associated Terms (BT, SELF, NT, RT)	E C01C003-00+ALL/IPC
BRO (MAN)	Complete Class	E C01C+BRO/IPC
BT	Broader Term (BT, SELF)	E C01F001-00+BT/IPC
CORE (COR)	Core Codes for the Advanced Level IPC Code	E G08C0019-22+CORE/IPC
ED	Complete title of the SELF term and IPC manual edition	E C01F001-00+ED/IPC
HIE	Hierarchy Term (Broader and Narrower Term) (BT, SELF, NT)	E C01B003-00+HIE/IPC
INDEX	Complete title of the SELF term	E C01F001-00+INDEX/IPC
KT	Keyword Term (catchwords) (SELF, KT)	E CYANOGEN+KT/IPC
NEXT	Next Classification	E C01C001-00+NEXT5/IPC
NT	Narrower Terms (SELF, NT)	E C01C+NT/IPC
PREV	Previous Classification	E C01C001-12+PREV10/IPC
RT (SIB)	Related Terms (SELF, RT)	E C01C003-20+RT/IPC
TI	Complete Title of the SELF Term and Broader Terms (BT, SELF)	E C01F001-00+TI/IPC

ECLA (/EPC) Thesaurus

This thesaurus is available in the /EPC search field (for ECLA codes). All relationship codes can be used with both the EXPAND and SEARCH commands.

Relationship Code	Content	Search Examples
ALL	All usually required terms (BT, SELF, CODE, DEF)	E C12M0001-34H2+ALL/EPC
AUTO **(1)**	Automatic relationship (BT, SELF, CODE, DEF)	E G01J003-443+AUTO/EPC
BT	Broader terms (BT, SELF)	E G01J0003-443+BT/EPC
CODE	Classification Code (SELF, CODE)	E MOVING SCRAPER+CODE/EPC
DEF	Definition (SELF, DEF)	E B65G0045-16+DEF/EPC
HIE	Hierarchy terms (all broader and narrower terms) (BT, SELF, DEF, NT)	E A01B0001+HIE/EPC
KT	Keyword terms (SELF, KT)	E LASER+KT/EPC
MAX	All associated terms	E G01J0003-44B+MAX/EPC
NEXT	Next classification within the same class (SELF, NEXT)	E A01B0001-24+NEXT/EPC
NEXT(n)	Next n classification within the same class	E A01B0001-24+NEXT3/EPC
NT	Narrower terms	E G05B0001-04+NT/EPC
PREV	Previous Code within the same class (SELF, PREV)	E G05B0019-418N1+PREV/EPC
PREV(n)	Previous n classifications within the same class	E G05B0019-418N1+PREV2/EPC
TI	Complete Title of the SELF Term and Broader Terms (BT, SELF)	E G05B0001-03+TI/EPC

(1) Automatic Relationship is SET OFF. In case of SET REL ON the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

CPC Thesaurus

This thesaurus is available in the /CPC search field. All relationship codes can be used with both the EXPAND and SEARCH commands.

Code	Content	Search Examples
ALL	All usually required terms (BT, SELF, CODE, DEF)	E C12M0001-005+ALL/CPC
AUTO **(1)**	Automatic relationship (BT, SELF, CODE, DEF)	E G01J003-443+AUTO/CPC
BT	Broader terms (BT, SELF)	E G01J0003-443+BT/CPC
CODE	Classification Code (SELF, CODE)	E CARTRIDGES+CODE/CPC
DEF	Definition (SELF, DEF)	E B65G0045-16+DEF/CPC
HIE	Hierarchy terms (broader and narrower terms) (BT, SELF, DEF, NT)	E A01B0001+HIE/CPC
KT	Keyword terms (SELF, KT)	E LASER+KT/CPC
MAX	All associated terms	E G01J0003-44+MAX/CPC
NEXT	Next classification within the same class (SELF, NEXT)	E A01B0001-24+NEXT/CPC
NEXT(n)	Next n classification within the same class	E A01B0001-24+NEXT3/CPC
NT	Narrower terms	E G05B0001-04+NT/CPC
PREV	Previous Code within the same class (SELF, PREV)	E G05B0019-00+PREV/CPC
PREV(n)	Previous n classifications within the same class	E G05B0019-00+PREV2/CPC
TI	Complete Title of SELF Term and Broader Terms (BT, SELF)	E G05B0001-03+TI/CPC

(1) Automatic Relationship is SET OFF. In case of SET REL ON the result of EXPAND or SEARCH without any relationship code is the same as described for AUTO.

DISPLAY and PRINT Formats

Any combination of formats may be used to display or print answers. Multiple codes must be separated by spaces or commas, e.g., D L1 1-5 TI PA. The fields are displayed or printed in the order requested.
The information of the latest publication is displayed by default. To display the content for all levels of the record you can combine all display fields and formats with the qualifier .M except FA, FAM, CFAM, LS, LS2, SCAN, and TRIAL. The default display format is STD.M, i.e., all publication levels of one family in the STN format.
For displaying a particular publication of a database record, you can simply add for certain display field the kind code to the appropriate display format, e.g. ALL.A. Fields that allow this are indicated by a number (3).

Hit-term highlighting is available for all fields. Highlighting must be ON during SEARCH to use the HIT, KWIC, and OCC formats.

Format	Content	Examples
AB (ABS)	Abstract	D TI AB 1-5
AI (AP) **(1)**	Application Information	D AI
AN	Accession Number	D L3 AN
CLM **(3)**	Claims	D CLM
CLMN **(2)**	Number of Claims	D CLMN
CPC	Cooperative Patent Classification	D CPC
DETD **(3)**	Detailed Description	D DETD
DETN **(2)**	Number of Paragraphs in DETD	D DETN
DT (TC)	Document Type	D DT
ED	Entry Date	D ED
EDTX	Entry Date of Fulltext	D EDTX
DED	Data Entry Date	D DED
DUPD	Data Update Date	D DUPD
EPC	European Patent Classification	D EPC
FA	Field Availability (for all publication levels)	D FA
GI	Graphic Image	D GI
GIS **(2)**	Graphic Image Size	D GIS
GIT **(2)**	Graphic Image Type	D GIT
IC	IPC (format contains ICM, ICS)	D IC
ICM	IPC, Main	D IC
ICS	IPC, Secondary	D ICS
IN (AU)	Inventor	D IN
IN.CNY	Inventor, Country	D IN.CNY
IPCI	IPC, Initial	D IPCI
IPCR	IPC, Reclassified	D IPCR
LA	Language	D LA
LAF	Language of Filing	D LAF
MCLM	Main Claim	D MCLM
PA (CS)	Patent Applicant/Patentee	D PA
PA.CNY	Patent Applicant, Country	D PA.CNY
PI (PN, PATS) **(1)**	Patent Information	D PI
PIT	Patent Information Publication Type	D PIT
PNO	Patent Number, Original Format	D PNO
PRN (PRAI) **(1,5)**	Priority Information	D PRN
PRNO (PRAO) **(2)**	Priority Number, Original Format	D PRNO
PRYF	Priority Year, First	D PRYF
RLI (RLN)	Related Patent Information	D RLI
TI	Title	D TI
UP	Update Date	D UP
ALL **(1)**	AN, ED, EDTX, UP, DED, DUPD, TI, IN, IN.CNY, PA, PA.CNY, LAF, LA, DT, PIT, PI, AI, RLI, PRAI, IPC, CPC, EPC, AB, DETD, CLM	D ALL
ALLG **(1)**	ALL, plus graphic image	D ALLG
IALL **(1)**	ALL, indented with text labels	D IALL
DALL **(1)**	ALL, delimited for post processing	D DALL
IALLG **(1)**	IALL, plus graphic image	D IALLG
APPS **(1)**	AI, RLN, PRAI	D APPS

DISPLAY and PRINT Formats (cont'd)

Format	Content	Examples
BIB **(1)**	AN, ED, EDTX, UP, DED, DUPD, TI, IN, IN.CNY, PA, PA.CNY, LAF, LA, DT, PIT, PI, AI, RLI, PRAI, IPC, CPC, EPC	D BIB
BIBG **(1)**	BIB, plus graphic image	D BIBG
IBIB **(1)**	BIB, indented with text labels	D IBIB
IBIBG **(1)**	IBIB, plus graphic image	D IBIBG
BRIEF **(1)**	AN, ED, EDTX, UP, DED, DUPD, TI , IN, IN.CNY, PA, PA.CNY, LAF, LA, DT, PIT, PI, AI, RLI, PRAI, IPC, CPC, EPC, AB, MCLM	D BRIEF
BRIEFG **(1,4)**	BRIEF, plus graphic image	D BRIEFG
IBRIEF **(1)**	BRIEF, indented with text labels	D IBRIEF
IBRIEFG **(1,4)**	BRIEFG, indented with text labels	D IBRIEFG
FAM **(1)**	AN, table of patent family information (from INPADOCDB)	D FAM
CFAM **(1)**	AN, Condensed family format (from INPADOCDB)	D CFAM
CPC.TAB	CPC, in tabular version	D CPC.TAB
IND	ED, IPC (ICM, ICS, IPCI, IPCR), CPC, EPC	D IND
IPC	International Patent Classification (ICM, ICS, IPCI, IPCR)	D IPC
IPC.TAB	IPC, IPC.KW, IPC.VER, in tabular version	D IPC.TAB
LS	Legal Status (from INPADOCDB)	D LS
LS2	Legal Status (from NPADOCDB), detailed version with display headers	D LS2
MAX (ALL.M) **(1)**	AN, ED, EDTX, UP, DED, DUPD, TI, IN, IN.CNY, PA, PA.CNY, LAF, LA, DT, PIT, PI, AI, RLI, PRAI, IPC, CPC, EPC, AB, DETD, CLM, FA for all levels of publication	D MAX
MAXG (ALLG.M) **(1)**	MAX, plus graphic image	D MAXG
IMAX (IALL.M) **(1)**	MAX, indented with text labels	D IMAX
IMAXG (IALLG.M) **(1)**	IMAX, plus graphic image	D IMAXG
RE	Citations (from INPADOCDB)	D RE
SCAN **(4)**	TI (random display without answer numbers)	D SCAN
STD **(1,6)**	AN, ED, EDTX, UP, DED, DUPD, TI , IN, IN.CNY, PA, PA.CNY, LAF, LA, DT, PIT, PI, AI, RLN, PRAI, IPC, CPC, EPC	D STD
STDG **(1)**	STD, plus graphic image	D STDG
ISTD **(1)**	STD, indented with text labels	D ISTD
ISTDG **(1)**	ISTD, plus graphic image	D ISTDG
TRIAL (TRI, SAM, SAMPLE, FREE)	ED, EDTX, UP, DED, DUPD, TI, FA, DETN, CLMN	D TRIAL
TX	DETD, CLM	D TX
HIT	Hit term(s) and field(s)	D HIT
KWIC	Up to 50 words before and after hit term(s) (KeyWord-In-Context)	D KWIC
OCC	Number of occurrences of hit term(s) and field(s) in which they occur	D OCC

(1) By default, patent numbers, application and priority numbers are displayed in STN Format. To display them in Derwent format, enter SET PATENT DERWENT at an arrow prompt. To reset display to STN Format, enter SET PATENT STN.
(2) Custom display only.
(3) You can combine this display field with the qualifier .PK (Patent Kind Code) to display the content for a certain publication level of a record, e.g. CLM.B2.
(4) SCAN must be specified on the command line, i.e., D SCAN or DISPLAY SCAN.
(5) If priority information is not available for a certain document, this information is taken from the application information of this document and marked with an asterisk (*).
(6) The default display format is STD.M, i.e., all publication levels of one family in the STD format.

SELECT, ANALYZE, and SORT Fields

The SELECT command is used to create E-numbers containing terms taken from the specified field in an answer set.

The ANALYZE command is used to create an L-number containing terms taken from the specified field in an answer set.

The SORT command is used to rearrange the search results in either alphabetic or numeric order of the specified field(s).

You can combine all fields except FA with the qualifier .M to SELECT/ANALYZE the content of all publication levels.

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Abstract	AB	Y	N
Accession Number	AN	Y	Y
Application Country	AC	Y	N
Application Date	AD	Y	N
Application Information	AI (AP, APPS)	Y **(2)**	N
Application Year	AY	Y	N
Claims	CLM	Y	N
CPC Classification	CPC	Y	Y
Detailed Description	DETD	Y **(3)**	N
Document Type	DT	Y	Y
Entry Date	ED	Y	Y
Entry Date Full Text	EDTX	Y	N
European Patent Classification	EPC	Y	N
Field Availability	FA	Y	N
Graphic Image Size	GIS	Y	N
Graphic Image Type	GIT	Y	Y
International Patent Classification	IC	Y	N
Inventor	IN (AU)	Y	Y
Inventor, Country	IN.CNY	Y	Y
IPC (ICM, ICS, IPCI, IPCR)	IPC	Y	Y
IPC, Advanced Level Symbols	IPC.A	Y **(4)**	N
IPC, Advanced Level Symbols for Invention	IPC.AI	Y **(4)**	N
IPC, Initial	IPCI	Y	Y
IPC, Main	ICM	Y	Y
IPC, Reclassified	IPCR	Y	Y
IPC, Reform	IPC.REF	Y	N
IPC, Secondary	ICS	Y	Y
Language	LA	Y	Y
Language of Filing	LAF	Y	Y
Main Claim	MCLM	Y	N
Number of Claims	CLMN	Y	N
Number of Paragraphs in DETD	DETN	Y	N
Occurrence Count of Hit Terms	OCC	N	Y
Patent Assignee/Patentee	PA (CS)	Y	Y
Patent Assignee, Country	PA.CNY	Y	Y
Patent Country	PC	Y	Y
Patent Information Publication Type	PIT	Y	Y
Patent Kind Code	PK	Y	Y
Patent Number	PI (PN, PATS)	Y (default)	Y
Patent Number, Original	PNO	Y	Y
Patent Number/Kind Code	PNK	Y	N
Pre-IPC8 Symbols from the ICM and first IPC8 values from 2006-present	IPC.F	Y **(4)**	Y
Priority Country	PRC	Y	Y
Priority Date	PRD	Y	Y
Priority Date, First	PRDF	Y	Y

SELECT, ANALYZE, and SORT Fields (cont'd)

Field Name	Field Code	ANALYZE/ SELECT (1)	SORT
Priority Number	PRN (PRAI)	Y	Y
Priority Number, Original	PRNO	Y	Y
Priority Year	PRY	Y	Y
Priority Year, First	PRYF	Y	Y
Publication Date	PD	Y	Y
Publication Year	PY	Y	Y
Related Patent Country	RLC	Y	Y
Related Application Number	RLN	Y	Y
Related Application Date	RLD	Y	Y
Related Application Year	RLY	Y	Y
Title	TI	Y	Y
Update Date	UP	Y	Y

(1) HIT may be used to restrict terms extracted to terms that match the search expression used to create the answer set, e.g., SEL HIT TI.
(2) Selects or analyzes application numbers with /AP appended to the terms created by SELECT.
(3) Appends /BI to the terms created by SELECT.
(4) Appends /IPC to the terms created by SELECT.

Sample Records

DISPLAY MAX (STN format)

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AN     2009055269   CNFULL  ED 20120210 UP 20120210 EDTX 20120210
TI     Oral insulin medicament and preparation method thereof
IN     NANRONG XUE, CN; ZHIJING HE, CN
PA     NANRONG XUE, CN
LAF    English
LA     English
DT     Patent; (Fulltext)
PIT    CNA UNEXAMINED APPLICATION FOR A PATENT FOR INV.
PI     CN 101590221            A    20091202
AI     CN 2009-10033603              20090624
PRAI   CN 2009-10033603              20090624
IPCI   A61K0038-28 [I,A]; A61K0047-38 [I,A]; A61P0003-10 [I,A]
AB
       Original
       The invention relates to an oral insulin medicament for treating type II
       diabetes, which contains insulin, primary bile acid, lecithin,
       cholesterol and bilirubin. The oral insulin medicament comprisesthe
       following components by weight: 1 weight portion of insulin, 30 to 100
       weight portions of primary bile acid, 100 to 300 weight portions of
       lecithin, 1 to 3 weight portions of cholesterol, 0.08 to0.8 weight
       portion of bilirubin, and 50 weight portions of bile acid. …
DETD
       Oral administration insulin medicine and preparation method

       Area of technology

       This invention involves one kind of treatment TYPE II diabetes' oral
       administration insulin medicine and preparation method.

       Technological background

       Insulin (insulin, Ins.) as falling the blood sugar biochemical medicine
       is used to treat diabetes to have 88 years history, until now still for
       the insulin dependant form diabetes (IDDM) patient's first choice
       medicine, was more and more much non-insulin dependant form saccharorrhea
       got sick the (NIDDM) patient's essential medicine. At present the
       clinical care favors uses the insulin to TYPE II diabetes (2DM) …

CLM
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CNFULL

1. Oral administration insulin medicine, its characteristic is to include the insulin, the first-level cholic acid, lecithin, cholesterol and bilirubin, various components' weight shares are: Insulin 1 …

2. Oral administration insulin medicine that according to claim 1 station, its characteristic was said that the first-level cholic acid contained the good sulfur cholic acid sodium, glycocholic acid and goose deaeration taurocholic acid and/or the goose deaeration glycocholic acid.

AN 2009055269 CNFULL ED 20120210 UP 20120210 EDTX 20120210
TI Oral insulin medicine and preparation method thereof
IN NANRONG XUE; ZHIJING HE
PA NANRONG XUE
LAF English
LA English
DT Patent; (Fulltext)
PIT CNC GRANTED PATENT FOR INVENTION [FROM 19850401 UNTIL 20100406]
PI CN 100594929C C 20100324
AI CN 2009-10033603 20090624
PRAI CN 2009-10033603 20090624
IPCI A61K0038-28 [I,A]; A61K0047-38 [I,A]; A61P0003-10 [I,A]
AB

Original
The invention relates to an oral insulin medicament for treating type II diabetes, which contains insulin, primary bile acid, lecithin, cholesterol and bilirubin. The oral insulin medicament comprisesthe following components by weight: 1 weight portion of insulin, 30 to 100 weight portions of primary bile acid, 100 to 300 weight portions of lecithin, 1 to 3 weight portions of cholesterol, 0.08 to …

DETD

Oral administration insulin medicine and preparation method

Area of technology

This invention involves one kind of treatment TYPE II diabetes' oral administration insulin medicine and preparation method.

Technological background

Insulin (insulin, Ins.) as falling the blood sugar biochemical medicine is used to treat diabetes to have 88 years history, until now still for the insulin dependant form diabetes (IDDM) patient's …

CLM

1. Oral administration insulin medicine, its characteristic is to include the insulin, the first-level cholic acid, lecithin, cholesterol and …
2. Oral administration insulin medicine that according to claim 1 station, its characteristic was said that the first-level cholic acid contained the good sulfur cholic acid sodium, glycocholic acid and goose deaeration taurocholic acid and/or the goose deaeration glycocholic acid.

DISPLAY IBRIEFG

ACCESSION NUMBER: 2011290923 CNFULL
ENTRY DATE: 20120203
UPDATE DATE: 20120301
ENTRY DATE (FULLTEXT): 20120203
TITLE (ENGLISH): Splitter
PATENT APPLICANT(S): HANNSTAR DISPLAY CORPORATION
LANGUAGE OF FILING: Chinese
LANGUAGE OF PUBL.: Chinese
DOCUMENT TYPE: Patent; (Fulltext)
PATENT INFORMATION TYPE: CNU UTILITY MODEL APPLICATION [FROM 19850401 UNTIL 19921231] or REGISTERED UTILITY MODEL
PATENT INFORMATION: CN 202121929 U 20120118
APPLICATION INFO.: CN 2011-20239732 20110705
PRIORITY INFO.: CN 2011-20239732 20110705

IPC ORIGINAL: H05K0013 [I,A]

ABSTRACT (ENGLISH):

Machine translation

This utility model has about one kind of splitter, for separating a non-nondefective, uses a wire rod, to be relative to non-nondefective an angle, cuts into the non-nondefective a viscose level, to reduce contact resistance, but also provides one separation method.

MAIN CLAIM (ENGLISH):

1. Kinds of splitters, its characteristic lies in it for separating a non-nondefective, should the non-nondefective contain one On the part, a part as well as a viscose level located at should get up the part with this to get down the parts, should separate to suppose Prepares includes: A main platform, the load bearing should the non-nondefective;One the wire rod, establishes in should the non-nondefective first end, and has the same level to be high with this viscose level;A right platform, establishes right this main platform, this right platform fixes this wire rod an end;As well as A left platform, establishes left side of this main platform, this left platform fixes this wire rod another end;And this left platform and right platform successively, and repeatedly move toward should the non-nondefective second end,This second looks carefully regarding this first end, this wire rod passes should the non-nondefective second end.